

MODEL QUESTION PAPER

MFET2

I Semester M.TECH Examination, August 2011 VLSI TECHNOLOGY AND PROCESS MODELING

Time: 3 Hours

Max. Marks: 75

GROUP A : Answer any three questions.

- Q.1 Design a Bi-CMOS circuit for $Z=A+BC$.
- Q.2 What are the limits on logic levels and supply voltage due to noise?
- Q.3 Explain Latch up effect in CMOS circuit in n-well structure.
- Q.4 Construct a color-coded stick diagram to represent the design of the following integrated nMOS and CMOS structures and indicate pull up/pull down ratios in a selectively loadable dynamic register to hold one four-bit word parallel
- Q.5 List and explain scaling factors for device parameters (any five).

GROUP B : Answer any three questions.

- Q.6 Explain write and read operation for dynamic and static memory cells with diagrams.
- Q.7 Prove that P_g , P_a and P_t are scaled by $1/\beta^2$, α^2/β^2 and $1/\alpha^2\beta$, respectively.
- Q.8 Explain the general arrangement of a 4-bit arithmetic processor.
- Q.9 Explain the terms threshold voltage and threshold variation
- Q.10 Draw and explain switch logic implementation of JK flip-flop.

GROUP C : All Questions are Compulsory.

Q.11 Fill in the blanks

- (i) Total Capacitance $C_t =$ _____.
- (ii) Rise-time estimation for CMOS inverter is $T_r =$ _____.
- (iii) A logical expansion of the p-well and n-well approaches is the _____ fabrication process.
- (iv) KCL determines _____ current.
- (v) Metal-Metal spacing is _____ than poly-poly spacing.

Q.12 Multiple choice question.

- (i) What happens if V_{DS} is increased over saturation?
 - (a) Pinch-off
 - (b) Cut-off
 - (c) No change
 - (d) None of these
- (ii) The colour code for n-diffusion is _____.
 - (a) Red
 - (b) Blue
 - (c) Green
 - (d) Yellow
- (iii) Following scanning technique is used to reduce the test pattern generation costs and also to reduce the test data and test time.
 - (a) Level sensitive scan design
 - (b) Built in self test.
 - (c) Boundary scan test
 - (d) Compact test.
- (iv) Transconductance is measured in _____.
 - (a) Ohms
 - (b) Volts
 - (c) Amperes
 - (d) Mho or siemens
- (v) $1/\beta$ is the scaling factor for supply voltage V_{DD} and _____.
 - (a) V_{th}
 - (b) Parasitic capacitance
 - (c) Gate oxide thickness
 - (d) Channel length.

Q.13 True or false

- (i) G_m for a bipolar transistor is $I_c/kT/q$.
- (ii) CMOS technology has high input impedance.
- (iii) Interlayer capacitance and Peripheral capacitance are the types of Area capacitance.
- (iv) Bipolar devices are low voltage swing devices.
- (v) The p-channel MOS consists of lightly doped substrate of n - type silicon material.
